13th European WET Users Group Meeting
Friday, April 16, 2021; 14:00 – 18:20
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Welcome
13th European WET Users Group Meeting  
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Some Statistics:

313 registrations for CMP and WET UGM  
6 presentations CMP  
9 presentations Wet  
17 sponsors

Regions / countries:  
Europe, United States, Korea, Japan, Taiwan, China, Saudi Arabia
WET Processes: Session 1

Session Chair: Martin Kulawski, Advaplan, Espoo, Finland

14:00 Opening Remarks
Knut Gottfried
Fraunhofer ENAS & ErzM-Technologies, Chemnitz, Germany

14:10 The Digital Transformation at AP&S - from eSales to eService
Christoph Kluge, tepcon GmbH, Donaueschingen, Germany

14:35 Wet SiC-Metal-Etch - From Single-Wafer to Batch application
Stefan Zürcher, AP&S GmbH, Donaueschingen, Germany

15:00 Raider® Next Gen Process Capabilities; Electrochemical deposition, Cleans and Wet Etch, Imge Namal, Brandon Brooks, Gaeme Bell, Applied Materials GmbH, Feldkirchen, Germany

15:25 Increased process stability for selective Si P+/P- etching
Dr. Benedikt Risse, Harald Perchinig, Christian Kleindienst NexGen Wafer Systems, Villach, Austria

15:50 Coffee Break
WET Processes: Session 2

Session Chair: Marie Christin Wolff, Fraunhofer ISIT, Itzehoe, Germany

16:10 Wet Processes - An endless renewal of challenges
Jerome Daviot, TECHNIC, Saint-Denis, France

16:35 Stable Oxide-Free Silicon Wafer Surface with Optimized Si-H Terminations using a Novel HF-Last Wet Clean Technology
John Oshinowo, Bob Pagliaro, APET, Hamburg, Germany

17:00 Why to replace a filter – Lifetime limitations and replacement criteria
Jochen Ruth, Pall Corp., Dreieich, Germany

17:25 Removal of silica, boron and trace metals from UPW
Siddartha Sampath, Entegris Inc, Billerica, MA, USA

17:50 Quantum NXT - Water & Energy Savings with Stop Flow & Recirculation Technology
Nick Rose, Trebor International, Inc., West Jordan, UT, USA

18:15 Wet Session Final Remarks
Knut Gottfried
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Coffee Break
until 16:10
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Thank You: speakers
session chairs
attendees
sponsors

Next Meeting: October 2021, hopefully face-to-face

CMPUGM U.S.A.: NCCAVS - CMPUG Spring Virtual Meeting
April 22, 2021, 1:00 – 6:00 pm CDT

CAMP Meeting: August 2021